

REDUCING PHOTORESIST LINE EDGE ROUGHNESS
USING CHEMICALLY-ASSISTED REFLOW

Abstract of the Disclosure

Line edge roughness may be reduced by treating a patterned photoresist with a plasticizer. The plasticizer may be utilized in a way to surface treat the photoresist
5 after development. Thereafter, the plasticized photoresist may be subjected to a heating step to reflow the photoresist. The reflow process may reduce the line edge roughness of the patterned, developed photoresist.